Beneath the AVS Surface

November 2025 Member News & Updates

ABOUT AVS | NEED HELP | MyAVS

AVS Events Calendar

AVS Sponsored & Endorsed Events

15th International Workshop on Oxide Surfaces (IWOX XV)
January 11-16, 2026
Stowe, VT | Website

51st International Conference on the Physics and Chemistry of Surfaces and Interfaces (PCSI-51 2026)
January 25-29, 2026
Santa Fe, New Mexico | Website

NCCAVS 46th Annual Equipment Exhibition, NCCAVS Technical Symposium & Workshop/Tutorial & 13th Annual Student Poster Session
February 26, 2026
Fremont, CA | Website

Frontiers in Characterization and Metrology for Nanoelectronics (FCMN 2026)
March 16-19, 2026
Monterey, California | Website

Area Selective Deposition Workshop (ASD 2026)
March 29- April 1, 2026
Albany, NY | Website

ICMCTF'26- International Conference On Metallurgical Coatings & Thin Films
April 19-24, 2026

VIEW ALL EVENTS

International Workshop on Gallium Oxide and Related Materials (IWGO 2026)
August 2-7, 2026
College Park, Maryland | Website

Liquid Metal Processing and Casting Conference (LMPC)
September 20 - 24, 2026
Albuquerque, New Mexico | Website Coming Soon

AVS Board Meetings

Sunday, December 7, 2025
(Via Zoom)

Sunday, February 1, 2026
Cary, North Carolina (In conjunction with Publications Summit and visit with Publications Staff)

Sunday, April 19, 2026
San Diego, California (In conjunction with ICMCTF'26)

Sunday, July 26, 2026
(via Zoom)

Sunday, November 8, 2026

San Diego, CA | **Website**

AVS 26th International Conference on Atomic Layer Deposition (ALD 2026) featuring the 13th International Atomic Layer Etching Workshop (ALE 2026)
June 28-July 1, 2026
Tampa, Florida | **Website**

24th International Conference on Molecular Beam Epitaxy (ICMBE 2026)
July 12-16, 2026
University of Michigan, MI | **Website**

39th International Vacuum Nanoelectronics Conference (IVNC 2026)
July 13-17, 2026
Tokyo Kokubunji, Japan | Website Coming Soon

Pittsburgh, Pensylvania (In conjuction with the AVS 72nd International Symposium & Exhibition)

Career Resources

Featured Jobs

FAMU-FSU College of Engineering
Chair, Materials Science and Engineering Department

LPS Qubit Collaboratory
LQC Postdoctoral & Research Scientist Positions in Qubit Materials & Devices

University of Alabama at Birmingham
Assistant Professor - Physics of Materials under Extreme Conditions

University of British Columbia
Postdoctoral Positions in Quantum Materials (x2)

University of Chicago, Pritzker School of Molecular Engineering
Assistant Professor – Quantum Science & Engineering (Theoretical)

UW Madison
Assistant/Associate/Full Professor

AVS Career Center

Professional Development
Apply for Jobs - Post Jobs

CAREER CENTER

"The AVS Career Center has consistently been a cost effective source for qualified candidates in our recruiting efforts. Our AVS postings have attracted a wide range of applicants both domestic and international." -**Physical**

Electronics USA

Member News

Exciting News: AVS Digital Badges Are Here!

We're thrilled to announce that AVS has officially launched digital badging credentials in partnership with Credly — giving you a fresh, modern way to showcase your achievements!

If you recently took a National Short Course or were a National Awardee you've recently earned an AVS credential and you should have received an email from Credly inviting you to claim your digital badge and certificate.

Why Share?

Sharing your badge helps highlight your hard-earned skills and accomplishments — and it also shines a spotlight on AVS, expanding the visibility of our community and the value of AVS credentials.

Here's how to get the most out of your new badge:

- Add it to your LinkedIn profile under Certifications or share it in a post.
- Include it in your email signature to enhance your professional brand.
- Post it on other social media platforms like X (Twitter), Facebook, or Instagram.

When posting, be sure to tag AVS — we love to celebrate your achievements and may even reshare your post!

This is more than just a credential — it's a way to tell your professional story. Congratulations on your achievement, and welcome to the next level of recognition with AVS!

Other Membership News:

Ensure that your AVS Membership is up to

Gift AVS Platinum Membership

Start the year off with an act of mentorship by gifting your colleague or student an AVS Platinum Membership. Help expand their network and yours.

Update Your MyAVS Profile

Please make sure that you keep your membership current with up to date information such as Chapter and Division affiliations.

MyAVS

date. Login to MyAVS to see when your membership is up for nenewal.

In Memorium

Prof. Jindřich Musil

January 19, 1934 - October 31, 2025
AVS Member 2013- 2018

Sadly, we learned that Prof. Jindřich Musil passed away unexpectedly on October 31, 2025.

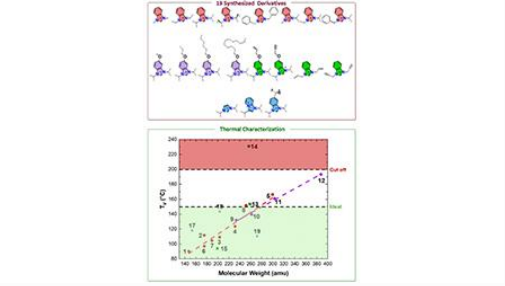
Prof. Musil was born on January 19, 1934. In 1966 he received his Ph.D. degree, in 1979 his DrSc. in Physical and Mathematical Sciences at the Czechoslovak Academy of Sciences in Prague, and in 1995 he received the title of Professor of Applied Physics at the University of West Bohemia in Pilsen. His main research areas were electromagnetic fields, propagation of electromagnetic waves in various media, radar technology, millimeter wave interferometers, plasma physics, thermonuclear fusion in systems with magnetic and inertial confinement of plasma, high-power pulsed gas lasers, plasma chemistry, and physics of thin films and coatings. In recent years, his research has focused mainly on PVD and PACVD of thin films, high-speed reactive magnetron sputtering and the development of new advanced nanocomposite coatings with unique properties, new technological processes for their formation and new advanced systems for the production of new advanced thin films and coatings. He received the State Prize of Czechoslovakia for the development of plasma technologies for the formation of thin films in Czechoslovakia (1984), three prizes in physics for the interaction of high-power microwaves with plasma (1973), for the high-power pulsed photodissociation iodine laser (1986) and for the reactive deposition of stoichiometric and non-stoichiometric titanium nitride layers (1990) from the Czechoslovak Academy of Sciences.

In 2014, he received the R.F.Bunshah Award for "*pioneering contribution to the development of advanced nanocomposite coatings with increased hardness and crack resistance*" from the Advanced Surface Engineering Division of the American Vacuum Society. In 2022, he received the international Leading Scientist Award for his long-term research activity at the 18th International Conference on Plasma Surface Engineering in Erfurt (Germany). In 2023, he received the K.-T. Rie Award for his long-term research activities at the 13th Asian-European International Conference on Plasma Surface Engineering in Busan (South Korea). He has published more than 280 peer-reviewed scientific articles, which have been cited more than 8850 times without self-citations, and his h-index is 48. He is the co-author of 1 book, 3 monographs, 10 book chapters, and 43 patents. He has given 125 invited lectures at leading international conferences abroad.

Professor Musil will be remembered as a giant in the international surface engineering and thin film community.

Publications Highlights

Benzimidazolium Hydrogen Carbonate Salts- Investigation of Thermal Properties in the Context of Small Molecule Inhibitors



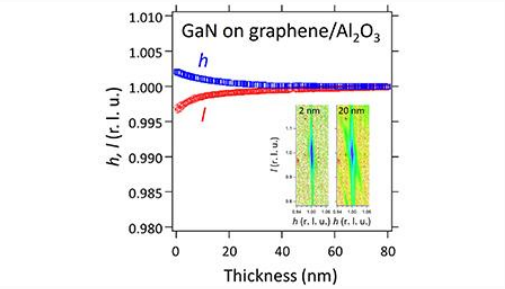
READ ARTICLE

Publication: *J. Vac. Sci. Technol. A* 43, 062403 (2025)

Authors: Eden Goodwin, Jordan N. Bentley, Maram Bakiro, Mark D. Aloisio, Justin Lomax, Ishwar Singh, Alex J. Veinot, Ahmadreza Nezamzadeh, Paul Ragogna, Cathleen M. Crudden, Seán T. Barry

The thermal properties of N-heterocyclic carbenes (NHCs) are of interest as these species are attracting attention for use as small molecule inhibitors (SMIs) in area-selective atomic layer deposition. Free carbenes are known to be generated from the thermolysis of their bicarbonate salts along with one stoichiometric equivalent of water and carbon dioxide byproduct. The liberated NHC volatilizes into the gas phase during heating and is delivered to a surface. Thermal analysis of 19 different NHC derivatives demonstrates the influence of the steric bulk of substituents at nitrogen on the activation temperature and volatility of NHCs. Increasing molecular weight leads to decreased volatility, while increasing the steric bulk of the N-alkyl substituents affects precursor activation temperatures. The thermal window measured for these NHC derivatives makes them readily amenable to vapor deposition processes. The data underscore that NHCs are versatile and stable species with significant potential applications in surface modification and as next-generation SMIs.

Testing Strain Relaxation During Thin Film Growth Using Remote Epitaxy



READ ARTICLE

Publication: [Real-time x-ray diffraction analysis of GaN remote epitaxy on sapphire substrates covered with directly grown graphene] *Journal of Vacuum Science & Technology B*, Vol. 43, No. 5, Sept/Oct 2025

Authors: Takato Oda, Yuta Fukui, Shota Yokozawa, Noboru Ohtani, Takuo Sasaki, and Hiroki Hibino

Adding a graphene or hexagonal boron nitride interlayer between the substrate and epitaxial layer reduces lattice strain on thin films and increases quality.

Gallium nitride (GaN) thin films have many applications in high-performance electronic and optoelectronic devices. Typically, these thin films are grown on a substrate, such as silicon or sapphire, and in some cases are exfoliated to produce a free-standing film. However, exfoliation is technically challenging, and even when it is possible, the process can introduce mechanical damage or defects in the separated film or the underlying substrate, which limits its practicality for reliable free-standing thin-film production.

In contrast, remote epitaxy introduces an interlayer between the thin film and the substrate, which makes separating them easier. The epitaxial layer is bound to the substrate only through weak van der Waals forces, allowing the substrate to be reused and lowering costs. In addition, the weaker binding results in reduced strain from lattice mismatch, resulting in more flexibility and higher-quality films.

In the AVS *Journal of Vacuum Science & Technology B*, researchers from Kwansei Gakuin University and the National Institutes for Quantum Science and Technology in Japan explored the lattice deformation of GaN thin films grown on substrates with and without an interlayer.

“Owing to the absence of dangling bonds, these 2D layers weaken the interfacial interaction, allowing the overgrown film to relax its lattice more freely,” said author Hiroki Hibino. “As a result, even on lattice-mismatched substrates, fewer defects are introduced, leading to high crystalline quality.”

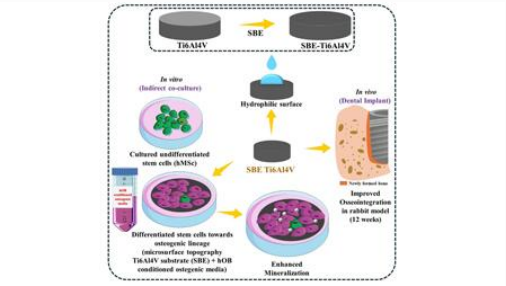
To test the process of lattice deformation, the team grew GaN thin films on sapphire substrates, first without an interlayer and then with graphene and hexagonal boron nitride (hBN) as interlayers. They probed the formation of these films using real-time X-ray diffraction.

“Sapphire is a widely used substrate for GaN epitaxy, and its polar Al-O bonds also favor GaN remote epitaxy through 2D interlayers,” said Hibino. “Graphene/sapphire and hBN/sapphire were selected to investigate how the presence or absence of polar bonding in different 2D interlayers affects remote epitaxy.”

They found that the presence of these interlayers facilitated early-stage lattice relaxation, with graphene being the most effective. However, the resulting thin films were discontinuous and exhibited a mixture of wurtzite (WZ) and zinc blende crystal phases.

“As a next step, we plan to optimize the growth conditions and control the nucleation density to improve the uniformity of GaN remote epitaxial films and promote the stable growth of the WZ phase,” said Hibino. “The exfoliated ultrathin GaN films could open new opportunities for flexible and transparent electronic and optoelectronic applications.”

Surface Modifications and Biochemical Signals Improve Bone–Implant Integration



READ ARTICLE

Publication: [Human osteoblast derived biochemical cues and microsurface topography modulate osteogenesis *in vitro* and *in vivo*](#) *Biointerphases*, Vol. 20, No. 5, Sep. 2025

Authors: Deepa Mishra, Anne Bernhardt, Michael Gelinsky, and Bikramjit Basu

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This paper is part of the Biointerphases Special Topic Collection: Biointerphases in India.

In vitro and in vivo experiments bridge the gap between physical surface and biochemical modulations to develop better implants for bone integration.

Exploring how to improve bone implants has wide-reaching benefits. Numerous studies have explored applications of multipotent mesenchymal stem cells (MSCs) in regenerative medicine. Separately, implantology emphasizes design features and surface topography. Bridging the gap between optimizing physical surface and biochemical modulations could help develop implants that facilitate better and faster bone integration.

A team from the Indian Institute of Science and the Technical University of Dresden investigated the effects of indirect co-cultures and surface engineering on titanium alloy implants with *in vitro* and *in vivo* rabbit experiments, publishing their work in Biointer*phases*. They determined that soluble factors secreted by human osteoblasts stimulate stem cell differentiation and calcium phosphate mineralization and that surface modifications of implants promote bone-like matrix formation.

“Collectively, these results indicate that microtopographical features and osteoblast-derived biochemical signals work synergistically to improve bone–implant integration, although the *in vivo* evidence primarily supports the role of surface modification,” said author Deepa Mishra. *In vitro*, the team evaluated five distinct conditions comprising different experimental and control substrate and media combinations. They cultured human MSCs under defined conditions to systematically attribute the cellular responses elicited by each substrate-media interaction. Expansion medium and standard osteogenic differentiation media served as controls. Conditioned osteogenic medium (cOBM), combining fresh media and media previously used to grow human osteoblasts, was the experimental indirect co-culture treatment. Prior cellular consumption makes cOBM partially nutrient-depleted, but rich in biochemical signals that promote osteogenic differentiation.

The researchers tested two titanium alloy surfaces: one sandblasted and acid-etched, and one polished smooth. They quantified cell growth through lactate dehydrogenase and DNA assays, and measured cell morphology, alkaline phosphatase (ALP) activity, and calcium phosphate deposition.

While neither cOBM nor the titanium alloy significantly increased ALP activity on its own, samples treated with both had substantially more calcium phosphate deposition, suggesting higher osteogenic differentiation.

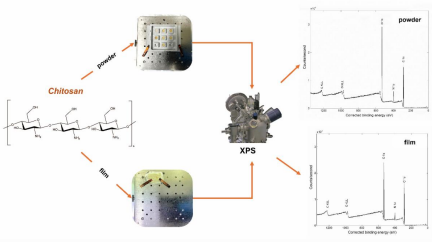
Despite causing decreased cell proliferation, cOBM’s ability to drive stem cells toward osteogenic differentiation and mineralization can still be beneficial for implant integration if properly managed.

In vitro results were reflected *in vivo* — rabbit femurs treated with rough titanium alloy implants showed higher bone growth than femurs treated with as-machined implants and control commercial implants.

“Practically, that suggests implants or surface treatments that present both topographical cues and osteoblast-like biochemical signals could shorten healing time, increase early bone–implant contact, and reduce failure rates — especially in compromised patients,” said Mishra. “It also raises the possibility of coating strategies that deliver osteoblast-derived factors or mimetics at the implant site.”

Mishra plans to identify the specific active factors in the cOBM, investigate cell–cell contact effects and paracrine dynamics in a direct co-culture, and conduct targeted *in vivo* studies to test implants coated in active factors.

XPS Spectra of Chitosan Powder and Film Acquired by Monochromatic Al Kα x-ray Source



Publication: Surf. Sci. Spectra 32, 024008 (2025)

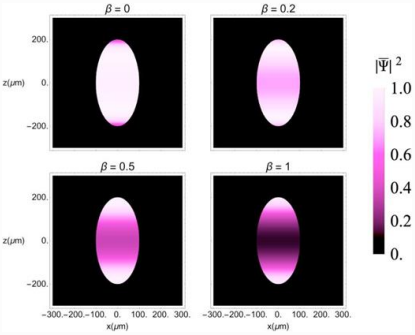
Author: G. Casula, D. Biggio, B. Elsener, A. Rossi, and M. Fantauzzi,

Visit our Website

Chitosan, a polysaccharide containing −OH and $-NH_2$ functional groups, is gaining attention from researchers due to its potential as a sorbent for metal ions. Preliminary results from a national priority project confirmed that chitosan can effectively remove toxic elements from polluted water and recover metals of high economic value, such as rare earth elements (REEs). In this submission from authors at the Università di Cagliari, XPS is used for characterizing chitosan sorbents after contact with solutions containing neodymium, gadolinium, samarium, and praseodymium to better understand the mechanism underlying the recovery of rare earth elements. In this work, the photoelectron core level spectra and valence band spectra obtained from a commercial chitosan powder and a film made up with the same powder are presented. In addition, x-ray induced Auger electron spectra of oxygen, O *KLL*, are included.

Consider submitting your XPS, AES, LEIPS, BIS, ToF-SIMS, SE, UV-vis, or LEIS data to *SSS* and joining a list of scientists and researchers who have contributed important analytical reference information that surface scientists and lab analysts need. Technique specific templates and other submission information can be found **here**.

Geometric Potential for a Bose–Einstein Condensate on a Curved Surface



Publication: AVS Quantum Sci. 7, 033203 (2025)

Authors: Sheilla M. de Oliveira and Natália Salomé Móller

READ ARTICLE

We compute the ground state of a Bose–Einstein condensate confined on a curved surface and unravel the effects of curvatures. Starting with a general formulation for any smooth surface, we apply it to a prolate ellipsoid, which is inspired by recent bubble trap experiments. Using only elementary tools, we perform a perturbative approach to the Gross–Pitaevskii equation and a general Ansatz, followed by a dimensional reduction. We derive an effective two-dimensional equation that includes a curvature-dependent geometric potential. We compute the ground state using the Thomas–Fermi approximation and, for an isotropic confinement, we find that the highest accumulation of atoms happens in the regions with the greatest difference between the principal curvatures. For a prolate ellipsoid, this accumulation happens on the equator, which is contrary to previous findings that describe accumulation on the poles of a bubble trap. Finally, we explain the reasons for this difference: the higher accumulation of atoms on the poles happens due to anisotropies in the confinement, while the higher accumulation on the equator happens exclusively due to the geometric properties of the surface.

Publications Announcements

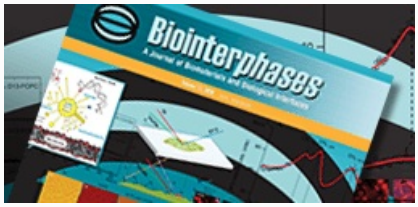
AVS Quantum Science (AQS)

Browse Issues | **Scilights** | **Press Releases**
Special Topics & Calls for Papers

AQS WEBSITE

Biointerphases (BIP)

X: Biointerphases
BlueSky : Biointerphases
LinkedIn : Biointerphases



BIP WEBSITE

- Celebrating the 20th Anniversary of Biointerphases **Extended Deadline: December 31, 2025**
- Tutorials in Sum-Frequency Generation Spectroscopy **Deadline: December 22, 2025**
- Biomimetics of Biointerfaces **Deadline: February 1, 2026**

Journal of Vacuum Science & Technology A (JVST A)

X: JVST A & B
BlueSky : JVST A & B
LinkedIn : JVST A & B

JVST A WEBSITE

- Phase Change Materials: Fundamentals, Innovations, and Applications **Deadline: December 3, 2025**
- High Entropy Alloys **Deadline: December 15, 2025**
- Atomic Layer Deposition & Atomic Layer Etching **EXTENDED Deadline: January 19, 2026**

Journal of Vacuum Science & Technology B (JVST B)

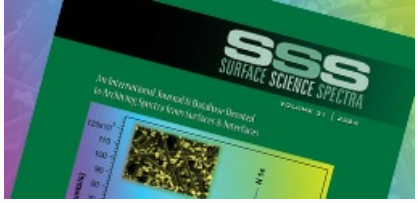
X: JVST A & B
BlueSky : JVST A & B
LinkedIn : JVST A & B

JVST B WEBSITE

- Spotlight on Early-Career Breakthroughs in Nanotechnology **Deadline: June 9, 2026**

Surface Science Spectra (SSS)

X: Surface Science Spectra
BlueSky : Surface Science Spectra
LinkedIn : Surface Science Spectra



SSS WEBSITE

- ToF-SIMS of Homogeneous Materials
  Deadline: May 20, 2026

Event Announcements

15th International Workshop on Oxide Surfaces (IWOX XV)

January 11-16, 2026
Stowe, Vermont
Website

The Fifteenth International Workshop on Oxide Surfaces (IWOX XV) will be held January 11-16, 2026. Since its inception in 1999, IWOX has been the preeminent venue for reporting and discussing breakthroughs in the field of oxide surface science. Since then, it has been held every two years, rotating between Asia, Europe and North America. The meeting brings together specialists in the field to present and discuss cutting-edge research on oxides and their surfaces and interfaces. The scientific topics will include: oxide reactivity and catalysis, oxide–liquid interfaces, oxidation and corrosion, oxide thin film growth and applications, supported oxide and metal clusters, surface structure and property relationships, electrochemistry, and energy

conversion and storage applications. Students and postdoc participation is strongly encouraged.

The meeting will be highlighted by invited speakers from around the world that span the breath of oxide surface fundamentals and applications.

Invited Speakers:

- Liney Arnadottir, Oregon State, USA
- Jan Balajka, TU Vienna, Austria
- Anjelika Kuhnle, Bielefeld, Germany
- Eranda Nikolla, Michigan, USA
- Jeong Park, KAIST, Korea
- Nini Pryds, TU Denmark, Denmark
- Peter Shushko, PNNL, USA
- Kelsey Stoerzinger, Minnesota, USA
- Fan Yang, Shanghai Tech, China
- Xiao Zhao, Stanford, USA
- Guangwen Zhou, Binghamton, USA

51st Conference on the Physics and Chemistry of Surfaces and Interfaces (PCSI-51)

January 25 - January 29, 2026
Santa Fe, New Mexico
Website

Late News Abstract Submission Deadline: December 2, 2025

The 51st Conference on the Physics and Chemistry of Surfaces and Interfaces (PCSI-51) will be held at the La Fonda Hotel in Santa Fe, New Mexico, USA, from Sunday afternoon, January 25, 2026, through Thursday noon, January 29, 2026.

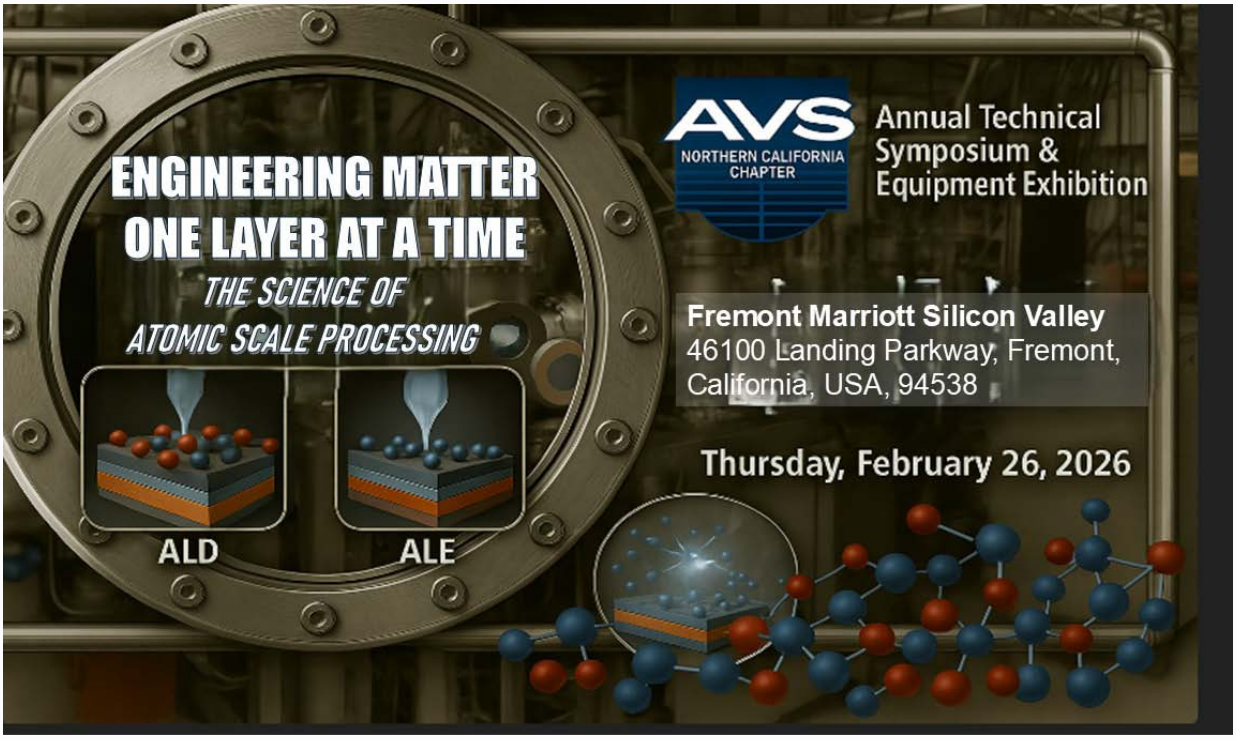
The annual PCSI conference is devoted to achieving a fundamental understanding of the physical, chemical, biological, structural, optical, magnetic, and electrical properties of surfaces and interfaces. These studies include novel growth processes and interfacial phenomena, new characterization tools, transport, and functionality of the structures for future devices.

Generous amounts of discussion time will be included in the program in order to emphasize the workshop character and to stimulate the exchange of new ideas.

SUBMIT ABSTRACT

NCCAVS 46th Annual Equipment Exhibition, NCCAVS Technical Symposium & Workshop/Tutorial & 13th Annual Student Poster Session

February 26, 2026
Fremont, California
Website



The Northern California Chapter AVS - NCCAVS 46th Annual Equipment Exhibition will be held in conjunction with the NCCAVS Technical Symposium & Workshop/Tutorial and 13th Annual Student Poster Session.

The Exhibition showcases products and services of companies supporting vacuum-related industries. The theme of the Symposium is "*Engineering Matter One Layer at a Time: The Science of Atomic Scale Processing*." The symposium will provide an international forum for academic researchers, industrial practitioners and engineers from around the world for the exchange of information on state-of-the-art research and include a workshop with speakers from academia and industry focusing on Atomic Layer Deposition and Atomic Layer Etching. There will also be a Student Poster Session to round out this annual event. Some highlights include:

- Largest Attendance of any AVS Chapter or Division
- Workshops from industry subject matter experts
- Speaker events at capacity
- Opportunities to speak with aspiring professionals during the Student Poster Session
- Extended hours provide ample time to engage all attendees
- Lunch, evening reception, and cocktails provided at no cost to attendees

Free to Attend – Advance Registration Coming Soon!

Exhibit and Sponsorship Registration Available - Register Today!!

For more information please visit the **NCCAVS Website**.

NCCAVS Sponsorship/Exhibit Registration

International Conference on Frontiers of Characterization and Metrology for Nanoelectronics (FCMN)

March 16-19, 2026
Monterey, California
Website

The 2026 **International Conference on Frontiers of Characterization and Metrology for Nanoelectronics (FCMN)** will be held at the Monterey Marriott in Monterey, CA from March 16-19, 2026.

The FCMN will bring together scientists and engineers interested in all aspects of the characterization technology needed for nanoelectronic materials and device research, development, integration, and manufacturing. All approaches are welcome: chemical, physical, electrical, magnetic, optical, in situ, and real-time control and monitoring. The semiconductor industry is evolving rapidly: the conference will highlight major issues and provide critical reviews of important materials and structure characterization and nearline/inline metrology methods, including hardware, data analysis, and AI and machine learning, as the industry both extends the technology deep into the nanoscale and increases the diversity of devices and systems.

The conference consists of formal invited presentation sessions and poster sessions for contributed papers. The poster papers cover new developments in materials and structure characterization/metrology down to the nanoscale. The conference began in 1995, and this meeting is the 15th in the series.

Area Selective Deposition Workshop (ASD 2026)

March 29- April 1, 2026
Albany, New York
Website

The ASD Workshop was initiated in 2016 to provide a scientific communication channel to learn and exchange about selective deposition techniques. It has since offered a forum for open discussions between researchers from academia and industry. The meeting will include one day of Tutorials followed by the Workshop at ETEC Building (University at Albany). The last day of the workshop will highlight the state of the art of SC devices and processes at NY state with invited presentation from our main industrial partners at the NY CREATES' Albany NanoTech Complex.

The 2026 **Area Selective Deposition Workshop (ASD 2026)** will take place **March 29-April 1**, 2026, at the University at Albany in New York, but it will be in two different locations:

- March 29-31, 2026: ETEC Building
- April 1, 2026: NY CREATES' Albany NanoTech Complex

52nd International Conference on Metallurgical Coatings and Thin Films (ICMCTF 2026)

April 19-24, 2026
San Diego, California
Website

Late News Abstract Submission Deadline: February 23, 2026

"Surface Engineering: Shaping Future Materials"

The **52nd International Conference on Metallurgical Coatings and Thin Films (ICMCTF 2026)** will be held at the **Town & Country Resort, San Diego, California, USA, from April 19-24, 2026**. ICMCTF is the premier international conference in the field of thin film deposition, characterization, and advanced surface engineering, promoting a global exchange of ideas and information among scientists, technologists, and manufacturers. The ICMCTF 2026 technical sessions will feature an overarching theme that emphasizes materials, surface engineering, processes, and applications relevant to the development of future materials, and will include a Topical Symposium focused on sustainability. The Conference includes more than 90 high-profile invited speakers, in over 50 sessions, across technical symposia, plenary and keynote lectures, short courses, an awards program, and daily social networking events.

A major exhibition of equipment, materials, technical literature, and new technologies is a key part of the conference. Attendees from all over the world come to present their findings, exchange ideas, share insights, make new friends, and often establish collaborations. The Conference typically draws 500 attendees.

Secure Your Visa Early: Due to increasing delays in securing visas it is strongly encouraged that you begin this process immediately to ensure approval. **Please click here for additional information and assistance**. Should you need an invitation letter, please contact **icmctf@icmctf.org** as early as possible to ensure you receive your visa well in time for the meeting.

Technical Program, Registration, Housing and the Mobile App will be launching in early December

SUBMIT ABSTRACT

AVS 26th International Conference on Atomic Layer Deposition (ALD 2026) featuring the 13th International Atomic Layer Etching Workshop

(ALE 2026)

June 28- July 1, 2026
Tampa, Florida
Website

Call for Abstracts Deadline: February 5, 2026

The **AVS 26th International Conference on Atomic Layer Deposition (ALD 2026) featuring the 13th International Atomic Layer Etching Workshop (ALE 2026)** will be a three-day meeting dedicated to the science and technology of atomic layer controlled deposition of thin films and atomic layer etching. Since 2001, the ALD conference has been held alternately in the United States, Europe and Asia, allowing fruitful exchange of ideas, know-how and practices between scientists. The conference will take place Sunday, June 28-Wednesday, July 1, 2026, at the JW Marriott Water Street, Tampa, Florida.

As in past conferences, the meeting will be preceded (Sunday, June 28) by one day of tutorials and perspectives and a welcome reception. Sessions will take place (Monday-Wednesday, June 29-July 1) along with an industry tradeshow. All presentations will be audio-recorded and provided to attendees following the conference (posters will be included as PDFs). Anticipated attendance is 700+. **View List of Invited Speakers**

SUBMIT ABSTRACT

AVS Corporate Members

To learn more, please visit the **AVS Corporate Membership Website** or contact **Angela Klink**, 212-248-0200, ext. 221.

Agilent Technologies
American Institute of Physics
Anderson Dahlen - Applied

Integrated Engineering Software
Intlvac Thin Film
ION-TOF USA, Inc.

RF VII, Inc.
SPECS Surface Nano Analysis GmbH

Vacuum Division
ATLANT 3D Nanosystems
BellowsTech
Duniway Stockroom, Corp.
Entegris
Gamma Vacuum
Hiden Analytical, Inc.
HVA, LLC
Kratos Analytical
Kurt J. Lesker Company
Mack Vacuum Technologies, Inc.
Oregon Physics LLC
Pfeiffer Vacuum
Physical Electronics
Reynard Corporation
Staib Instruments, Inc.
Sumitomo (SHI) Cryogenics of America, Inc.
Super Conductor Materials, Inc.
Thermo Fisher Scientific, Inc.
UC Components, Inc.
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